



Supplementary Material

Pseudo-Interface Switching of a Two-Terminal TaO_x/HfO₂ Synaptic Device for Neuromorphic Applications

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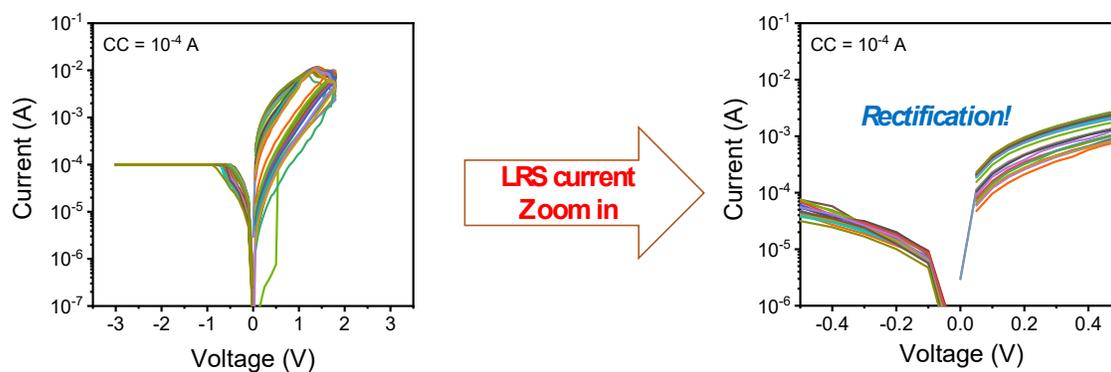


Figure S1. Rectifying I-V characteristics of the TaO_x/HfO₂ memristor in the LRS at CC of 10⁻⁴ A.

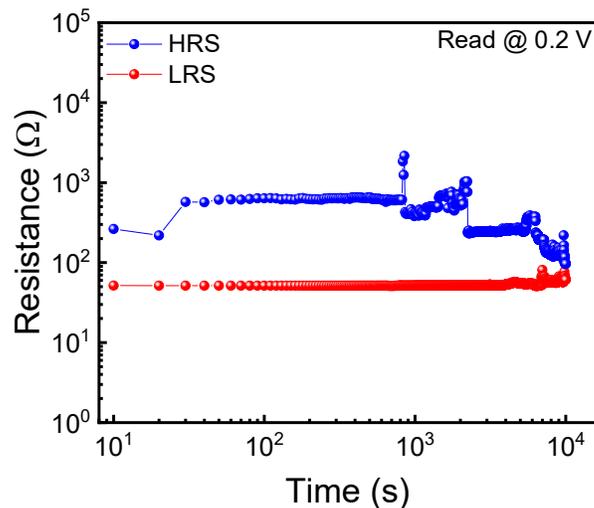


Figure S2. Retention test for interface-type switching of the TaO_x/HfO₂ memristor.



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